

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1-3. (cancelled)

4. (currently amended) A method of manufacturing an in-plane switching liquid crystal display having thin film transistors on a substrate, scan lines and signal lines connected to the thin film transistors and longitudinally and latitudinally crossing each other, and common wiring formed by the same layer as the scan lines and generating electric fields substantially parallel to the substrate between a common electrode connected to the common wiring and covering the signal lines partially via an interlayer insulating film formed on the thin film transistors, and pixel electrodes connected to the thin film transistors, the method comprising the steps of:

forming a first inorganic insulating film on at least source and drain electrodes of the thin film transistors,

forming first contact holes in said first inorganic insulating film for connecting the common wiring and the common electrode to each other, and second contact holes in said first inorganic insulating film for connecting the thin film transistors and the pixel electrodes to each other using at least dry etching,

forming a second inorganic insulating film on the first inorganic insulating film,

forming third contact holes in said second inorganic insulating film so as to be superposed on the first contact holes, and fourth contact holes in said second inorganic insulating film so as to be superposed on the second contact holes,

forming a conductive film on the second inorganic insulating film,

forming the common electrode connected to the common wiring via the first and third contact holes, and

forming the pixel electrodes connected to the thin film transistors via the second and fourth contact holes.

5. (original) A method according to claim 4, wherein:

the third contact holes are formed inside the first contact holes while the fourth contact holes are formed inside said second contact holes.

6. (currently amended) A method of manufacturing an in-plane switching liquid crystal display having thin film transistors on a substrate, scan lines and signal lines connected to the thin film transistors and longitudinally and latitudinally crossing each other, and common wiring formed by the same layer as the scan lines and generating electric fields substantially parallel to the substrate between a common electrode connected to the common wiring and covering the signal lines partially via an

interlayer insulating film formed on at least source and drain electrodes of the thin film transistors, and pixel electrodes connected to the thin film transistors, wherein:

the interlayer insulating film is formed by an inorganic insulating film, and

a thickness of the inorganic insulating film is set ~~to be greater than at least a thickness of a portion of the insulating film where~~ so that when contact holes for connecting the common wiring and the common electrode to each other are formed by dry etching, said thickness prevents pinholes created by said dry etching from penetrating through an entirety of said insulating film.

7. (new) The method according to claim 6, wherein said thickness is between 700 nm and 1000 nm.

8. (new) A method of manufacturing an in-plane switching liquid crystal display, comprising:

forming thin film transistors on a substrate;

forming scan lines and signal lines connected to the thin film transistors and longitudinally and latitudinally crossing each other;

forming common wiring as the same layer as the scan lines and generating electric fields substantially parallel to the substrate between a common electrode connected to the common wiring and covering the signal lines partially via an interlayer insulating film formed on at least source and drain electrodes of

the thin film transistors;

forming pixel electrodes connected to the thin film transistors; and

forming contact holes connecting the common wiring and the common electrode to each other, said contact holes being formed at a ratio of one contact hole to a plurality of the pixels with respect to the pixels divided and defined by the scan lines and the signal lines.